

L Number	Hits	Search Text	DB	Time stamp
2	99976	laser with (remov\$4 or pattern\$4 or etch\$4 or react\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/07 17:10
3	1590	(laser with (remov\$4 or pattern\$4 or etch\$4 or react\$4)) with evaporat\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/07 17:10
4	51	((laser with (remov\$4 or pattern\$4 or etch\$4 or react\$4)) with evaporat\$5) and 216/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/07 17:13
5	111	((laser with (remov\$4 or pattern\$4 or etch\$4 or react\$4)) with evaporat\$5) with (liquid or water or aqueous)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/07 17:13
6	5	((laser with (remov\$4 or pattern\$4 or etch\$4 or react\$4)) with evaporat\$5) with (liquid or water or aqueous)) and 216/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/07 17:14
7	9	((laser with (remov\$4 or pattern\$4 or etch\$4 or react\$4)) with evaporat\$5) with (liquid or water or aqueous)) and 219/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/07 17:14
8	8	((laser with (remov\$4 or pattern\$4 or etch\$4 or react\$4)) with evaporat\$5) with (liquid or water or aqueous)) and 219/\$.ccls.) not ((laser with (remov\$4 or pattern\$4 or etch\$4 or react\$4)) with evaporat\$5) with (liquid or water or aqueous)) and 216/\$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/07 17:22
9	102	((laser with (remov\$4 or pattern\$4 or etch\$4 or react\$4)) with evaporat\$5) with (liquid or water or aqueous)) not (((laser with (remov\$4 or pattern\$4 or etch\$4 or react\$4)) with evaporat\$5) with (liquid or water or aqueous)) and 219/\$.ccls.) (((laser with (remov\$4 or pattern\$4 or etch\$4 or react\$4)) with evaporat\$5) with (liquid or water or aqueous)) and 219/\$.ccls.) not (((laser with (remov\$4 or pattern\$4 or etch\$4 or react\$4)) with evaporat\$5) with (liquid or water or aqueous)) and 216/\$.ccls.))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/07 17:22
10	32	((laser with (remov\$4 or pattern\$4 or etch\$4 or react\$4)) with evaporat\$5) with (liquid or water or aqueous)) not (((laser with (remov\$4 or pattern\$4 or etch\$4 or react\$4)) with evaporat\$5) with (liquid or water or aqueous)) and 219/\$.ccls.) (((laser with (remov\$4 or pattern\$4 or etch\$4 or react\$4)) with evaporat\$5) with (liquid or water or aqueous)) and 219/\$.ccls.) not (((laser with (remov\$4 or pattern\$4 or etch\$4 or react\$4)) with evaporat\$5) with (liquid or water or aqueous)) and 216/\$.ccls.)) and laser.ab.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/07 17:22

inventor name search in
PALM

3/7/04 AOA